Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S69	33	(hydrogen H2 "H.sub.2") with (nitrogen N2 "N.sub.2") with (fluorine F2 "F.sub.2") same (plasma etch$3) and etch$3 with (silane siloxane vinyltrimethoxysilane siloxane-containing TEOS HMDSO)	US-PGPUB; USPAT	OR	ON	2005/09/17 18:56
S70	2	(hydrogen H2 "H.sub.2") with (nitrogen N2 "N.sub.2") with (fluorine F2 "F.sub.2") same (plasma etch$3) same bcb	US-PGPUB; USPAT	OR	ON	2005/09/17 18:03
S71	1	("2002/0155639").URPN.	USPAT	OR	OFF	2005/09/17 18:08
S72	25	("20020052125" | "20020155639" | "4330384" | "4333793" | "4529860" | "4636281" | "4707218" | "4838991" | "5017403" | "5116460" | "5294296" | "5459099" | "5750441" | "5882535" | "5932491" | "6140171" | "6168726" | "6207583" | "6294314" | "6326302" | "6331380" | "6350675" | "6358838" | "6388226" | "6426300").PN. OR ("6699792").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/09/17 18:08
S73	25	S72 and ((hydrogen H2 "H.sub.2") (nitrogen N2 "N.sub.2") (fluorine F2 "F.sub.2") etch$3 silane siloxane vinyltrimethoxysilane siloxane-containing TEOS HMDSO bcb)	US-PGPUB; USPAT	OR	ON	2005/09/17 19:50

| S74 | 793 | (((nitrogen N2 "N.sub.2") with ((hydrogen H2 "H.sub.2") and (fluorine F2 "F.sub.2")))((hydrogen H2 "H.sub.2") with ((nitrogen N2 "N.sub.2") and (fluorine F2 "F.sub.2")))((fluorine F2 "F.sub.2") with ((nitrogen N2 "N.sub.2") and (hydrogen H2 "H.sub.2"))) ((hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj $3fluoride)) ((nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric)) ((nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF.sub.3" "CF.sub.3 H" "CH.sub.3 F" "CFH.sub.3"))) same (plasma etch$3) and etch$3 with (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite $2organic/$2organic $2organic-$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD) | US-PGPUB; USPAT | OR | ON | 2005/09/17 19:24 |

| S75 | 1743 | ((nitrogen N2 "N.sub.2") with (hydrogen H2 "H.sub.2" fluorine F2 "F.sub.2") (hydrogen H2 "H.sub.2") with (fluorine F2 "F.sub.2") (fluorine F2 "F.sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj $3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF.sub.3" "CF.sub.3 H" "CH.sub.3 F" "CFH.sub.3")) same (plasma etch$3) same (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite $2organic/$2organic $2organic-$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB) | US-PGPUB; USPAT | OR | ON | 2005/09/17 20:15 |

| S76 | 517 | ((nitrogen N2 "N.sub.2") with (hydrogen H2 "H.sub.2" fluorine F2 "F.sub.2") (hydrogen H2 "H.sub.2") with (fluorine F2 "F.sub.2") (fluorine F2 "F.sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj $3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF.sub.3" "CF.sub.3 H" "CH.sub.3 F" "CFH.sub.3")) with (plasma etch$3) with (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite $2organic/$2organic $2organic-$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB) | US-PGPUB; USPAT | OR | ON | 2005/09/17 19:34 |

S77	49	((nitrogen N2 "N.sub.2") with (hydrogen H2 "H.sub.2" fluorine F2 "F.sub.2") (hydrogen H2 "H.sub.2") with (fluorine F2 "F.sub.2") (fluorine F2 "F.sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj $3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF.sub.3" "CF.sub.3 H" "CH.sub.3 F" "CFH.sub.3")) near2 (plasma etch$3) with (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite $2organic/$2organic $2organic-$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB)	US-PGPUB; USPAT	OR	ON	2005/09/17 19:34

| S78 | 69 | ((nitrogen N2 "N.sub.2") with (hydrogen H2 "H.sub.2" fluorine F2 "F.sub.2") (hydrogen H2 "H.sub.2") with (fluorine F2 "F.sub.2") (fluorine F2 "F.sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj $3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF.sub.3" "CF.sub.3 H" "CH.sub.3 F" "CFH.sub.3")) with (plasma etch$3) near2 (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite $2organic/$2organic $2organic-$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB) | US-PGPUB; USPAT | OR | ON | 2005/09/17 19:35 |

S79	28	((nitrogen N2 "N.sub.2") with (hydrogen H2 "H.sub.2" fluorine F2 "F.sub.2") (hydrogen H2 "H.sub.2") with (fluorine F2 "F.sub.2") (fluorine F2 "F.sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj $3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF.sub.3" "CF.sub.3 H" "CH.sub.3 F" "CFH.sub.3")) with (plasma etch$3) near (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite $2organic/$2organic $2organic-$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB)	US-PGPUB; USPAT	OR	ON	2005/09/17 19:37
S80	45	S77 not S79	US-PGPUB; USPAT	OR	ON	2005/09/17 19:58
S81	39	S78 not (S77 S79)	US-PGPUB; USPAT	OR	ON	2005/09/17 19:59

| S82 | 4 | ("6331481" \| "6372636" \| "6429122").PN. OR ("6787446").URPN. | US-PGPUB; USPAT; USOCR | OR | OFF | 2005/09/17 20:04 |
| S83 | 12 | ("5459105" \| "5780163" \| "5814563" \| "5817572" \| "6059553" \| "6124154" \| "6187666" \| "6221755" \| "6228751" \| "6323142" \| "6451504").PN. OR ("6632746").URPN. | US-PGPUB; USPAT; USOCR | OR | OFF | 2005/09/17 20:06 |

| S84 | 179 | ((nitrogen N2 "N.sub.2") with (hydrogen H2 "H. sub.2" fluorine F2 "F.sub. 2") (hydrogen H2 "H.sub. 2") with (fluorine F2 "F. sub.2") (fluorine F2 "F. sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj $3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF. sub.3" "CF.sub.3 H" "CH. sub.3 F" "CFH.sub.3")) same (plasma etch$3) same (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite $2organic/$2organic $2organic-$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB) | EPO; JPO; DERWEN T; IBM_TDB | OR | ON | 2005/09/17 20:24 |

| S85 | 89 | ((nitrogen N2 "N.sub.2") with (hydrogen H2 "H.sub.2" fluorine F2 "F.sub.2") (hydrogen H2 "H.sub.2") with (fluorine F2 "F.sub.2") (fluorine F2 "F.sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj $3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF.sub.3" "CF.sub.3 H" "CH.sub.3 F" "CFH.sub.3")) with (plasma etch$3) with (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite $2organic/$2organic $2organic-$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB) | EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/09/17 20:17 |

| S86 | 1 | ((nitrogen N2 "N.sub.2") with (hydrogen H2 "H. sub.2" fluorine F2 "F.sub. 2") (hydrogen H2 "H.sub. 2") with (fluorine F2 "F. sub.2") (fluorine F2 "F. sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj $3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF. sub.3" "CF.sub.3 H" "CH. sub.3 F" "CFH.sub.3")) near (plasma etch$3) with (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite $2organic/$2organic $2organic-$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB) | EPO; JPO; DERWEN T; IBM_TDB | OR | ON | 2005/09/17 20:18 |

| S87 | 5 | ((nitrogen N2 "N.sub.2") with (hydrogen H2 "H. sub.2" fluorine F2 "F.sub. 2") (hydrogen H2 "H.sub. 2") with (fluorine F2 "F. sub.2") (fluorine F2 "F. sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj $3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H.CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF. sub.3" "CF.sub.3 H" "CH. sub.3 F" "CFH.sub.3")) with (plasma etch$3) near (silane siloxane vinyltrimethoxysilane. siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite $2organic/$2organic $2organic-$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB) | EPO; JPO; DERWEN T; IBM_TDB | OR | ON | 2005/09/17 20:18 |

| S88 | 10 | ((nitrogen N2 "N.sub.2") with (hydrogen H2 "H.sub.2" fluorine F2 "F.sub.2") (hydrogen H2 "H.sub.2") with (fluorine F2 "F.sub.2") (fluorine F2 "F.sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj $3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF.sub.3" "CF.sub.3 H" "CH.sub.3 F" "CFH.sub.3")) with (plasma etch$3) near2 (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite $2organic/$2organic $2organic-$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB) | EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/09/17 20:21 |

| S89 | 13 | ((nitrogen N2 "N.sub.2") with (hydrogen H2 "H.sub.2" fluorine F2 "F.sub.2") (hydrogen H2 "H.sub.2") with (fluorine F2 "F.sub.2") (fluorine F2 "F.sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj $3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF.sub.3" "CF.sub.3 H" "CH.sub.3 F" "CFH.sub.3")) near2 (plasma etch$3) with (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite $2organic/$2organic $2organic-$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB) | EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/09/17 20:22 |
| S90 | 8 | S89 not (S86 S87 S88) | EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/09/17 20:23 |

S91	70	S85 not (S86 S87 S88 S89)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/17 20:24
S92	15	S91 and etch$3	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/17 20:24

| S93 | 49 | ((nitrogen N2 "N.sub.2") with (hydrogen H2 "H. sub.2" fluorine F2 "F.sub. 2") (hydrogen H2 "H.sub. 2") with (fluorine F2 "F. sub.2") (fluorine F2 "F. sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj $3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF. sub.3" "CF.sub.3 H" "CH. sub.3 F" "CFH.sub.3")) same (etch$3) same (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite $2organic/$2organic $2organic-$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB) | EPO; JPO; DERWEN T; IBM_TDB | OR | ON | 2005/09/17 20:25 |
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